

DAFTAR PUSTAKA

- Amin H. and Culkin B., 1996, *High Solid Inorganic Chemicals Processing and Product Recovery*, New Logic International. Inc.
- Binns R., 2001, *The Titanium Revolution*, University of Bristol.
- Fadli A dan Komalasari, 2002, *Model Kinetika Pembuatan Titanyl Sulfat dengan Unreacted Core Model*, Prosiding Seminar Nasional Fundamental dan Aplikasi Teknik Kimia 2002, ITS, Surabaya.
- Fadli A dan Sunarno, 2002, *Model Kinetika Pembuatan Titanyl Sulfat Dari Mineral Ilmenit*, Prosiding Seminar Nasional Rekayasa Kimia dan Proses 2002, Undip, Semarang.
- Fadli A, 2001, *Kinetika Reaksi Destruksi Mineral Ilmenit dengan H_2SO_4 pada Proses Pembuatan Rutil (TiO_2) Sintetis*, Tesis, Pascasarjana UGM, Yogyakarta.
- Gambogi, J, 1997, *Titanium*, U. S. Geological Survey-Minerals Information.
- George, I W, 1993, *Synthetic rutile operations of RGC minerals sands limited at Capel and Narngulu WA*, **Australian Mining and Metallurgy**, 2, pp 1301-1302.
- Hecki F. and Wittkowski M., 1996, *Integrating Production and Environmental Protection, Optimal Filtration Processes Reduce Hazardous Waste*, **Lenser Filtration**.
- Hendratno A., 1999, *Pengembangan Industri Pertambangan di Wilayah DIY Bagian Selatan*, Prosiding Lokakarya Eksploitasi, Eksplorasi dan Pengolahan Sumberdaya Mineral, hal. 24, Fakultas Teknik, Jurusan Teknik Geologi, Universitas Gadjah Mada, Yogyakarta.
- Hoecker and Walter, 1997, *Process for Production of Synthetic Rutil*, US Patent 5.601.630.
- Ho, K.K., Mohanchandra, K.P. and Carman, G.P., 2002, *Examination of the Sputtering Profile of NiTi Under Target Heating Conditions*, Thin Solid Films, 413, p-p. 1-7.

Inoue, Hideaki , Odagari and Masahiro, 1998, *High Purity Titanium Production Process*, US Patent 5.772.724.

Ishigami, Takashi, Kawai, Mituo, Yagi and Noriaki, 2002, *Highly Purified Titanium Material, Method fo Preparation of it and Sputtering Target Using it*, US Patent 6.400.025.

Johnstone, R. E. and Thring, M. W., 1957, *Pilot Plants, Models and Scale-up Method in Chemical Engineering*, p.p. 66 - 71, McGraw-Hill Book Co., New York.

Kim S, Park, S and Jeung, Y, 1999, *Homogeneous Precipitation of TiO₂ Ultrafine Powders from Aqueous TiOCl₂ Solution*, **Journal of the American Ceramic Society**, **82**,4.

Kobata, A., Kusakabe, K dan Morooka S., 1991, *Growth and Transformation of TiO₂ Crystallites in Aerosol Reactor*, AICHE Journal, **37**, 3, 347 - 359.

Larsson, A, and Ruppi, S., 2002, *Microstructure and Properties of Ti(C,N) Coatings Produced by Moderate Temperature Chemical Vapour Deposition*, Thin Solid Films, **402**, p-p. 203-210.

Legrand-Buscema, C., Malibert, C. and bach, S., 2002, *Elaboration and Characterization of Thin Films of TiO₂ Prepared by Sol-Gel Process* , Thin Solid Films, **418**, p-p. 79-84.

Mackowski, S J and Reaveley, B,1993, *Synthetic rutile production at Tiwest Joint Venture, Chandala WA*, **Australian Mining and Metallurgy**, **2**, pp 1304-1307.

Miki-Yoshida, M., Collins-Martinez, V., Amezaga-Madrid, P. and Aguilar-Elguezabal, A., 2002, *Thin Films of Photocatalytic TiO₂ and ZnO₂ Deposited Inside a Tubing by Spray Pyrolysis*, Thin Solid Films, **419**, p.p. 60-64.

Othmer - Kirk, 1983, *Encyclopedia of Chemical Technology*, third edition, volume 23, A Wiley-Interscience Publication, John Wiley & Sons. Inc., New York.

Pierson, J.F., Tomasella, E. and Bauer, P., 2002, *Reactively Sputtered Ti-B-N Nanocomposite Films: Correlation Between Structure and Optical Properties*, Thin Solid Films, **408**, p.p. 26-32.

- Reed J. S., 1988, *Introduction to the Principles of Ceramic Processing*, A Wiley-Interscience Publication, John Wiley & Sons Inc., New York.
- Rosenberg, Harry, Winters, Nigel, Xu and Yu, 2001, *Titanium Crystal and Titanium*, US Patent 6.309.595.
- Searle, A. B. and Grimshaw, R. W., 1960, *The Chemistry and Physics of Clays and other Ceramic materials*, third edition, Ernest Benn Limited, London.
- Shaginyan, L.R., Misina, M., Zemek, J., Musil., Regent, F. and Britun, V.F., 2002, *Composition, Structure, Microhardness and Residual Stress of W-Ti-N Films Deposited by Reactive Magnetron Sputtering*, Thin Solid Films, 408, p-p. 136-147.
- Shreeve N., B. and Brink J., A., Jr., 1977, *Chemical Process Industries*, Forth edition, Mc Graw-Hill Book Company, New York.
- Song, C. F., Lu, M. K., Yang, P., Xu, D. and Yuan, D. R., 2002, *Structure and Photolumine Properties of Sol-Gel TiO₂-SiO₂ films*, Thin Solid Films, 413, p-p. 155-159.
- Sugiarto B., 2002, *Kristalisasi Garam MgSO₄ dari Air Laut*, Prosiding Seminar Nasional Fundamental dan Aplikasi Teknik Kimia 2002, ITS, Surabaya.
- Sumardi P. C., 1999, *Pembuatan Rutil (TiO₂) Sintetis dari Ilmenit Hasil Samping Penambangan Timah Bangka*, Prosiding Lokakarya Eksploitasi, Eksplorasi dan Pengolahan Sumberdaya Mineral, Fakultas teknik, Jurusan Teknik Geologi, Universitas Gadjah Mada, Yogyakarta.
- Tian, Y., Womack, M., Molian, P., Lo, C.C.H., Anderegg, J.W., and Russell, A.M., 2002, *Structure and Photolumine Properties of Sol-Gel TiO₂-SiO₂ Films*, Thin Solid Films, 418 p-p. 129-135.
- Thomas R., Mochizuki S., Mihara T., Ishida, T., 2002, *Preparation of Pb(Zr,Ti)O₃ Thin Films by RF-Magnetron Sputtering with Single Stoichiometric Target: Structural and Electrical Properties*, Thin Solid Films, 413, p-p. 65-75.
- Ting, C., Chen S. and Liu D., 2002, *Preferential Growth of Thin Rutile TiO₂ Films Upon Thermal Oxidation of Sputtered Ti Films*, Thin Solid Films, 402, p-p. 290-295.

- Vaz, F., Rebouta, L., Goudeau, P., Riviere, J.P., Schaffer, E., Kleer, G. and Bodmann, M, 2002, *Residual Stress States in Sputtered $Ti_{1-x}Si_xN_y$ Films*, Thin Solid Films, 402, p-p. 195-202.
- Waskitoaji, W., 1997, *Studi Tentang Pengaruh Perlakuan Mekanis pada Kristalisasi TiO_2 gel berhidrat*, IPT Technical Journal, 2,1, 21-25.
- Yanagisawa, K. and Ovenstone, J., 1999, *Crystallization of Anatase from Amorphous Titania Using the Hydrothermal Technique : Effect of Starting Material and Temperature*, J. Phys. Chem., B, 103, pp. 7781-7787
- Young, N. A., 1999, *Mechanisms and Kinetics in The Solid State*, Annu. Rep. Prog. Chem., Sect. A, 95, 507-533.